

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
ICHIRO TANAKA) : Examiner: Unassigned
Application Based on) : Group Art Unit: Unassigned
JP 250853/1999) :
Filed: Herewith) :
For: TWO-DIMENSIONAL PHASE) :
ELEMENT AND METHOD OF) :
MANUFACTURING THE SAME : August 31, 2000

Commissioner for Patents
Washington, D.C. 20231

PRELIMINARY AMENDMENT

Sir:

Prior to examination on the merits of the above-identified application, please amend the application as follows.

In the Claims:

Please amend claims 2-4, 6-13 and 15 as follows:

Sub B1
2. (Amended) A method of manufacturing a two-dimensional phase type element, comprising the steps of: forming[, on a substrate,] a first etching mask in a checkered pattern on a substrate; and